IN THE CLAIMS:

Please amend the claims as follows:

Claim 1 (Original): A back illuminated photodetector comprising:

a first conductor type semiconductor substrate;

a second conductive type doped semiconductor region provided in the first superficial

surface layer of the semiconductor substrate;

a recessed portion for incidence of to-be-detected light formed in the second surface of

the semiconductor substrate and in an area opposite the doped semiconductor region; and

a coating layer made of resin for transmitting the to-be-detected light, the coating layer

being provided on the second surface,

the coating layer being arranged in such a manner that the portion provided on the

recessed portion in the second surface is sunk lower than the portion provided on the outer edge

portion of the recessed portion.

Claim 2 (Original): The back illuminated photodetector according to Claim 1, further

comprising a supporting film provided on the first surface of the semiconductor substrate to

support the semiconductor substrate.

Claim 3 (Original): The back illuminated photodetector according to Claim 2, further

comprising a filling electrode penetrating through the supporting film and connected electrically

to the doped semiconductor region at the one end thereof.

Claim 4 (Currently amended): The back illuminated photodetector according to any one

of claims 1 to 3 to Claim 1, wherein a highly-doped semiconductor region with impurities of the

first conductive type added thereto at a high concentration is exposed across the entire side

surface of the semiconductor substrate.

Claim 5 (Currently amended): The back illuminated photodetector according to any one

of claims 1 to 4 to Claim 1, wherein a highly-doped semiconductor layer with impurities of the

first conductive type added thereto at a high concentration is provided in the bottom portion of

the recessed portion within the second superficial surface layer of the semiconductor substrate.

Claim 6 (Currently amended): The back illuminated photodector according to any one

of claims 1 to 5 to Claim 1, wherein a highly-doped semiconductor layer with impurities of the

first conductive type added thereto at a high concentration is provided in the second superficial

surface layer in the outer edge portion of the semiconductor substrate.